

Integration of a Cu₂O/ZnO heterojunction and Ag@SiO₂ into a photoanode for enhanced solar water oxidation

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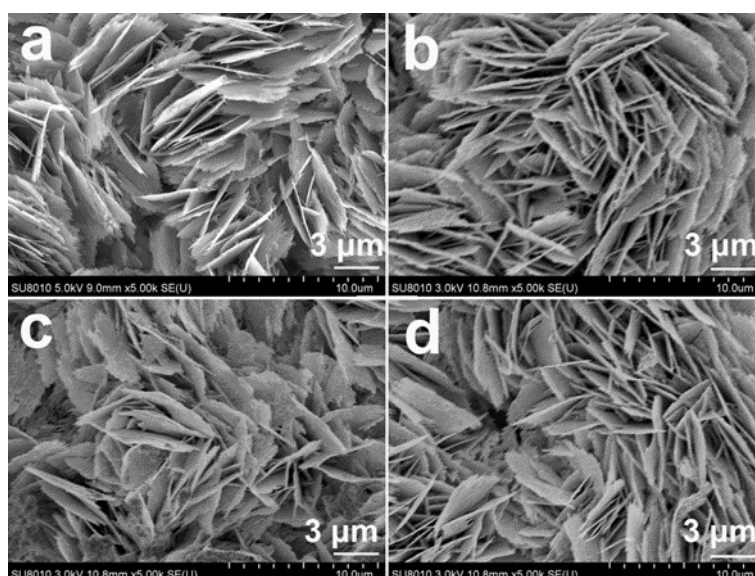


Fig. S1 The top-view SEM images of (a) FTO/ZnO, (b) FTO/ZnO/Cu₂O-1, (c) FTO/ZnO/Cu₂O-2 and (d) FTO/ZnO/Cu₂O-3 photoanodes.

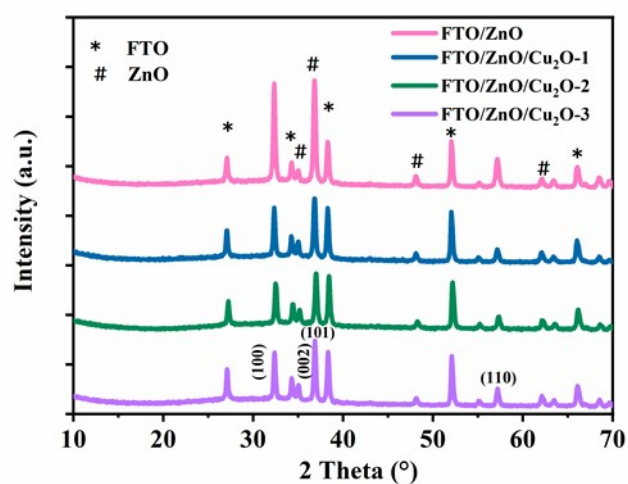


Fig. S2 The XRD patterns of FTO/ZnO, FTO/ZnO/Cu₂O-1, FTO/ZnO/Cu₂O-2 and FTO/ZnO/Cu₂O-3 photoanodes.

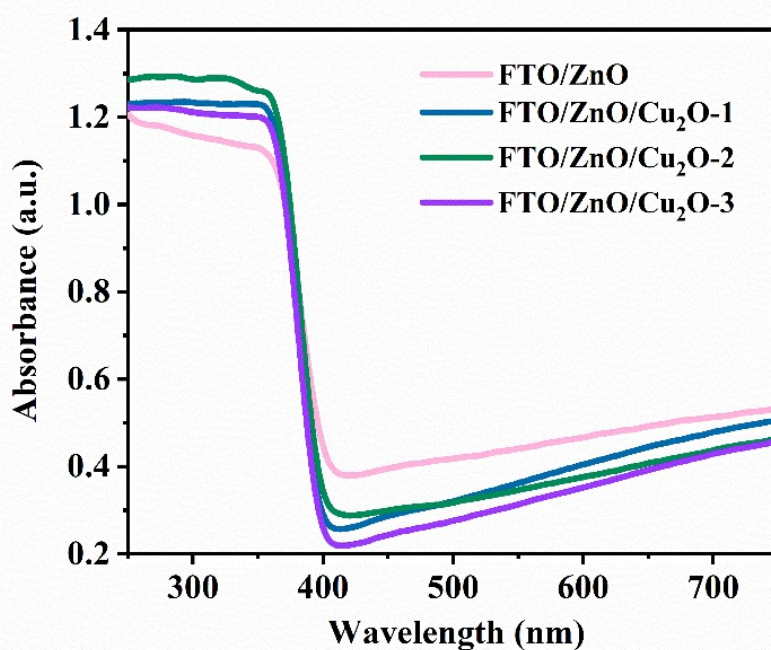


Fig. S3 The UV-vis diffuse reflectance spectra of FTO/ZnO, FTO/ZnO/Cu₂O-1, FTO/ZnO/Cu₂O-2 and FTO/ZnO/Cu₂O-3 photoanodes.

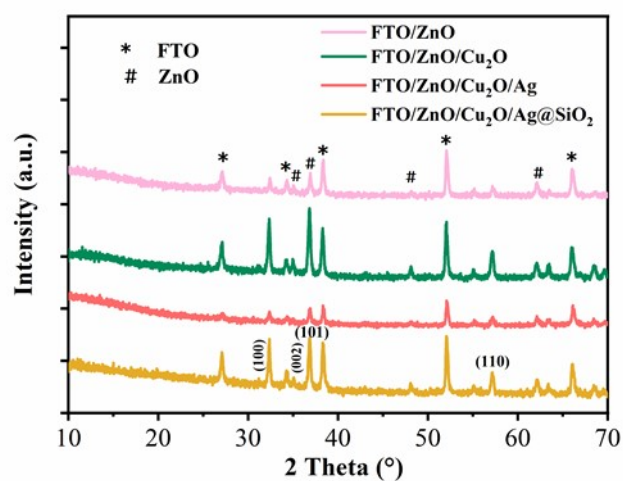


Fig. S4 The XRD patterns of FTO/ZnO, FTO/ZnO/Cu₂O, FTO/ZnO/Cu₂O/Ag and FTO/ZnO/Cu₂O/Ag@SiO₂ photoanodes.

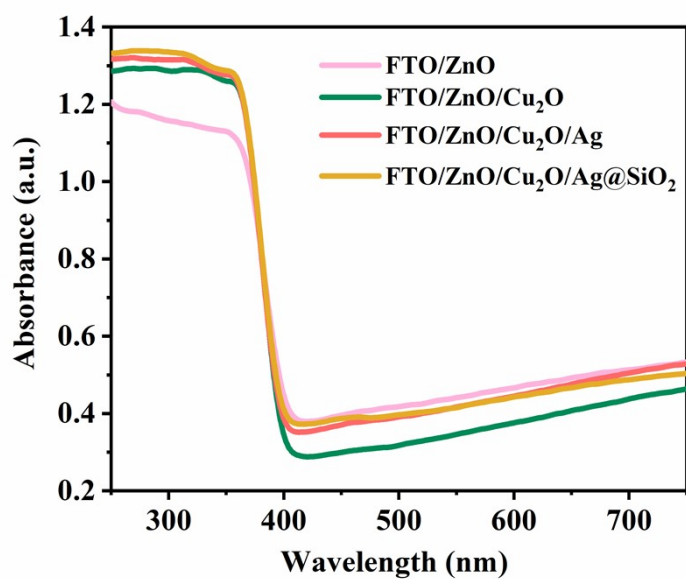


Fig. S5 The UV-vis diffuse absorbance spectra of FTO/ZnO, FTO/ZnO/Cu₂O, FTO/ZnO/Cu₂O/Ag and FTO/ZnO/Cu₂O/Ag@SiO₂ photoanodes.

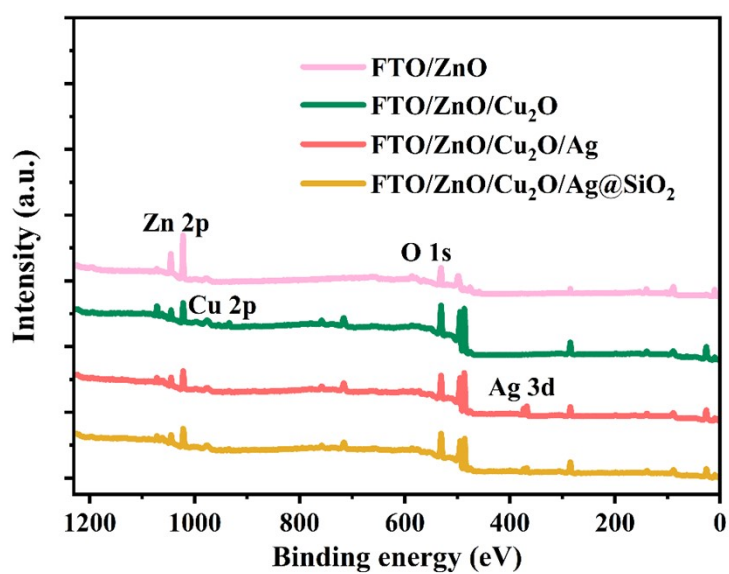


Fig. S6 XPS survey spectra of FTO/ZnO, FTO/ZnO/Cu₂O, FTO/ZnO/Cu₂O/Ag and FTO/ZnO/Cu₂O/Ag@SiO₂ photoanodes.

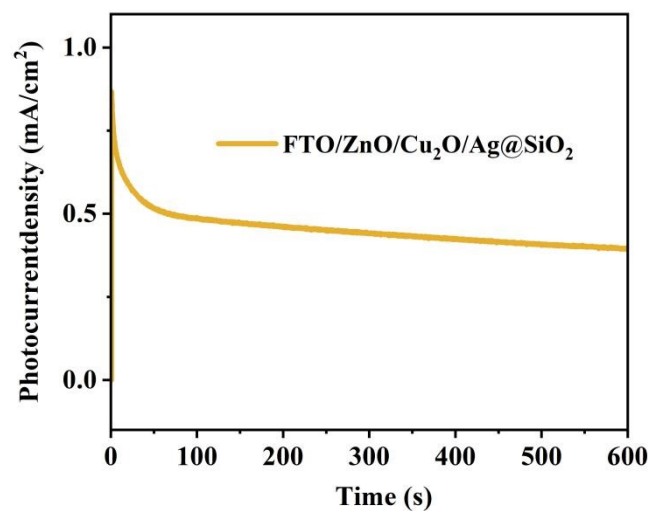


Fig. S7 $J-t$ curves of the FTO/ZnO/Cu₂O/Ag@SiO₂ photoanode at 1.23 V_{RHE} for stability study.

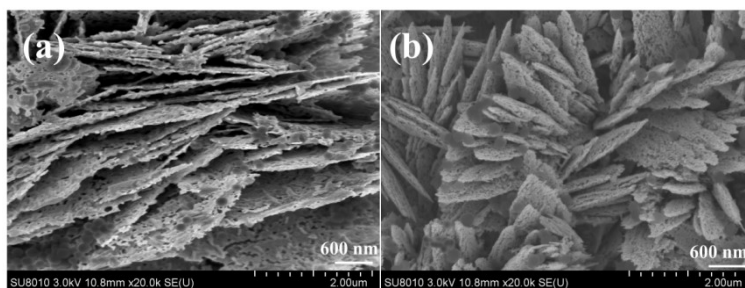


Fig. S8 The SEM images before and after stability test of FTO/ZnO/Cu₂O/Ag@SiO₂ photoanode.

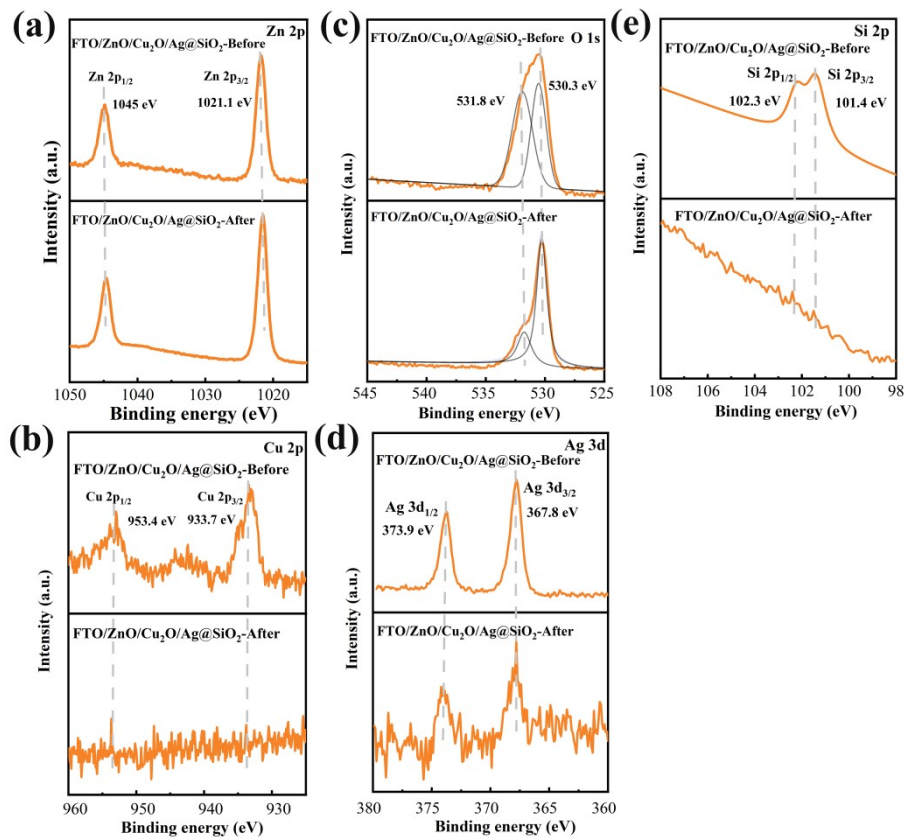


Fig. S9 The XPS spectra before and after stability test of FTO/ZnO/Cu₂O/Ag@SiO₂ photoanode.

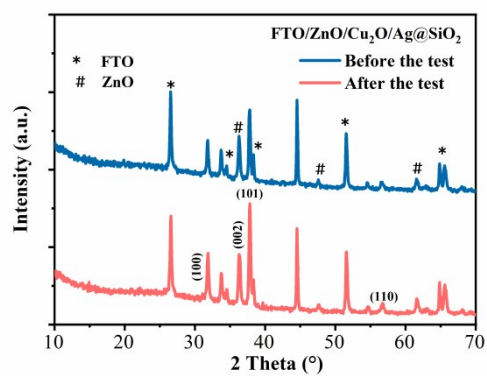
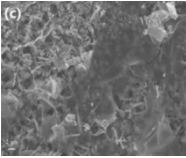
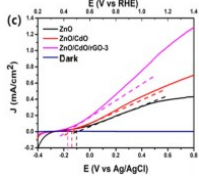
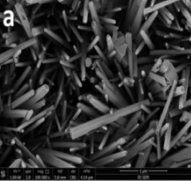
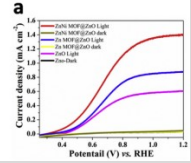
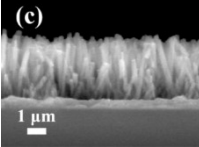
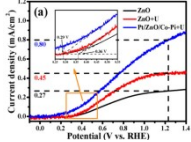
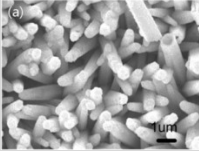
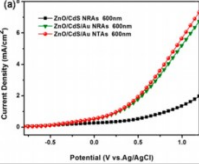
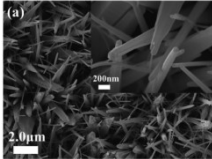
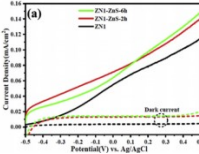
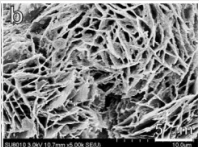
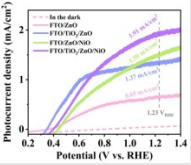
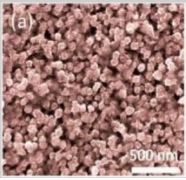
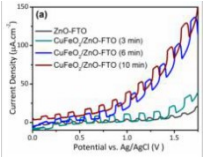
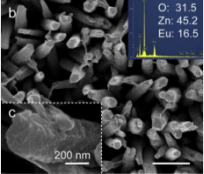
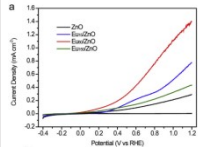
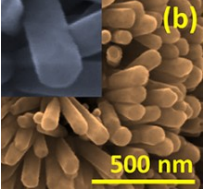
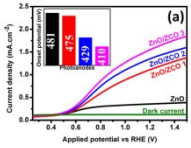
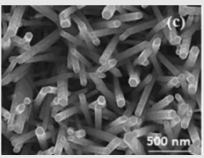
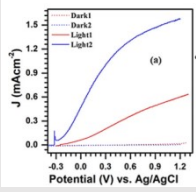
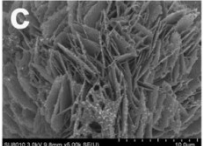
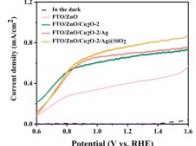


Fig. S10 The XRD patterns before and after stability test of FTO/ZnO/Cu₂O/Ag@SiO₂ photoanode.

Tab. S1 A comparison of the PEC-WS performances between the ZnO photoanodes in the related literature and our present FTO/ZnO/Cu₂O/Ag@SiO₂ photoanode.

Photoanode	Film texture	Optimized sample (<i>J-V</i> curves)	$J_{ph@1.23V}$ U_{on}	Testing conditions (Under AM 1.5G irradiation)	Key Method	Ref.
ZnO/CdO/rGO			0.38 mA/cm ² -0.2 V (vs. Ag@AgCl)	0.5 M Na ₂ SO ₄	thermal decomposition and spin coating	[1]
ZnNi MOF @ZnO			0.88 mA/cm ² 0.3 V _{RHE}	0.5M Na ₂ SO ₄	hydrothermal	[2]
Pt/ZnO/Co-Pi			0.8 mA/cm ² 0.07 V _{RHE}	0.1 M K ₃ PO ₄	hydrothermal and photoelectrode position	[3]
ZnO/CdS/Au			1 mA/cm ² -0.5 V (vs. Ag@AgCl)	0.25 M Na ₂ S 0.35 M Na ₂ SO ₃	chemical bath deposition and sulfuric acid corrosion	[4]
ZnO/ZnS			0.08 mA/cm ² -0.5 V (vs. Ag/AgCl)	0.5 M Na ₂ SO ₃	hydrothermal	[5]
FTO/TiO ₂ /ZnO/NiO			1.91 mA/cm ² 0.35 V _{RHE}	1.0 M NaOH	atomic layer deposition and immersion	[6]

ZnO/CuFeO ₂			54 $\mu\text{A}/\text{cm}^2$ 0.5 V (Ag/AgCl)	0.5 M Na ₂ SO ₄	spin coating and electrochemically depositing	[7]
Eu ₁₅₀ /ZnO			1.4 mA/cm ² 0.3 V _{RHE}	0.5M Na ₂ SO ₄	electrodeposition	[8]
ZnO/ZCO			1.58 mA/cm ² 0.5 V _{RHE}	0.5 M Na ₂ SO ₄	two-step aqueous chemical bath growth and electrodeposition	[9]
ZnO/CoO			1.25 mA/cm ² -0.3 V (vs. Ag@AgCl)	10, 30 mM borax with sodium hydroxide	ALD and CBD and ECD	[10]
FTO/ZnO/Cu ₂ O/Ag@SiO ₂			0.77 mA/cm ² 0.4 V _{RHE}	1.0 M NaOH	hydrothermal and immersion	This work

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